

[ABSTRACT]

Provided is a resist composition including a polymer compound (A1) having a constitutional unit (a10) represented by General Formula (a10-1), an onium salt-based acid generator (B1), a crosslinking agent (C), and a polynuclear phenol low-molecular-weight compound (Z) containing 5 or less phenyl groups, in which the resist composition has a solid content concentration of 15% by mass or greater. In the formula, R represents a hydrogen atom, an alkyl group having 1 to 5 carbon atoms, or a halogenated alkyl group having 1 to 5 carbon atoms. $Y^{a^{x1}}$ represents a single bond or a divalent linking group. $W^{a^{x1}}$ represents an aromatic hydrocarbon group which may have a substituent. n_{ax1} represents an integer of 1 or greater.

